



17/E (R312)

Patent
Attorney's Docket No. 018414-060

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Ref
6-2-94

In re Patent Application of

Jang F. CHEN

Application No.: 08/149,122

Filed: November 3, 1993

For: METHOD FOR IMPROVED
LITHOGRAPHIC PATTERNING IN A
SEMICONDUCTOR FABRICATION
PROCESS

Group Art Unit: 1503

Examiner: T. Mosley

AMENDMENT PURSUANT TO 37 C.F.R. §1.312(b)

Honorable Commissioner of Patents and Trademarks
Washington, D.C. 20231

Sir:

Prior to issuance of the above-identified application, in which the issue fee has been paid, kindly amend the above-identified application as follows:

IN THE CLAIMS:

Claim 1, line 14, change "Raleigh" to --Rayleigh--;
line 25, change "Raleigh" to --Rayleigh--.

Claim 12, line 13, change "Raleigh" to --Rayleigh--;
line 23, change "Raleigh" to --Rayleigh--.